

UV

Alignment error during resin hardening in UV-imprint lithography process

Insoo Park¹, Chongjin Won², Siyoul Jang², Hongjae Yim^{2, *#}, Jay I. Jeong(jayjeong@kookmin.ac.kr)²

Keywords: Nano-Imprint Lithography, Uv-Imprint Lithography, Alignment Process, LCD product process

1. (Nano-Imprint Lithography) 가

(1) LCD 가

가

가

3 가

UV 가

UV 가

UV 가

(2) LCD 가

UV 가

(3) 가

(4) 가

(MicroLenses Array) , LCD(Liquid Crystal Display) 가

가

가

UV 가

UV 가

2.

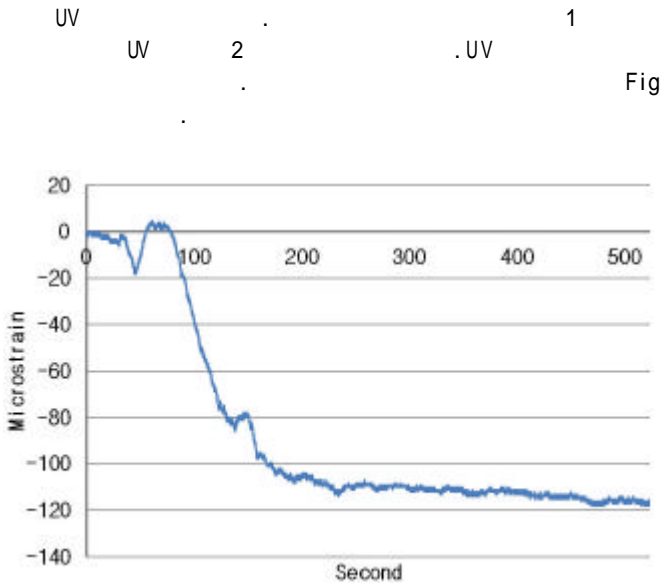


Fig. 1 Strain of resin in hardening process

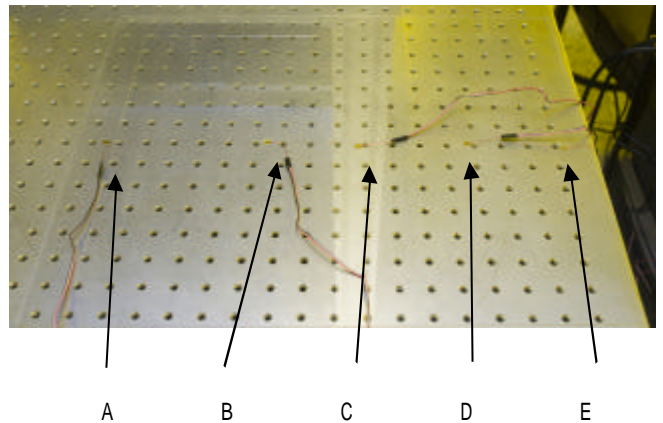


Fig. 2 Position of strain-gages in the mold

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3. UV 가

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470mm × 370mm × 0.5mm 가

400mm × 300mm × 0.67mm 가

Fig.2

A, B
10
2 UV

(10583).

7 UV

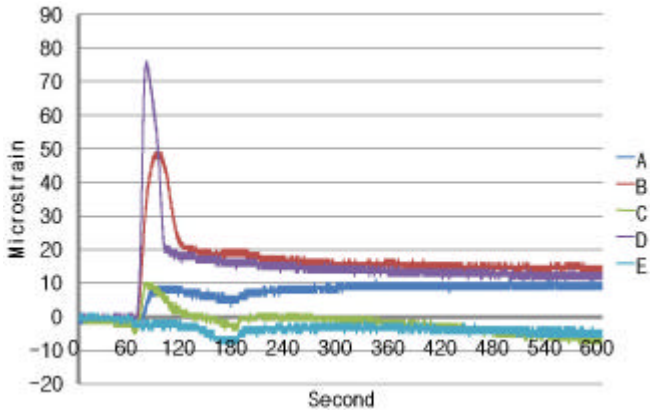


Fig.3 Strain of the mold in hardening process

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B D

가 가

가

, UV

가

가

4.

UV

LCD

UV

UV

가

LCD

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1

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UV

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